

Supporting Information

High-efficiency microwave absorbing performance originating from sufficient magnetic exchange coupling interaction and impressive dielectric loss

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Figures

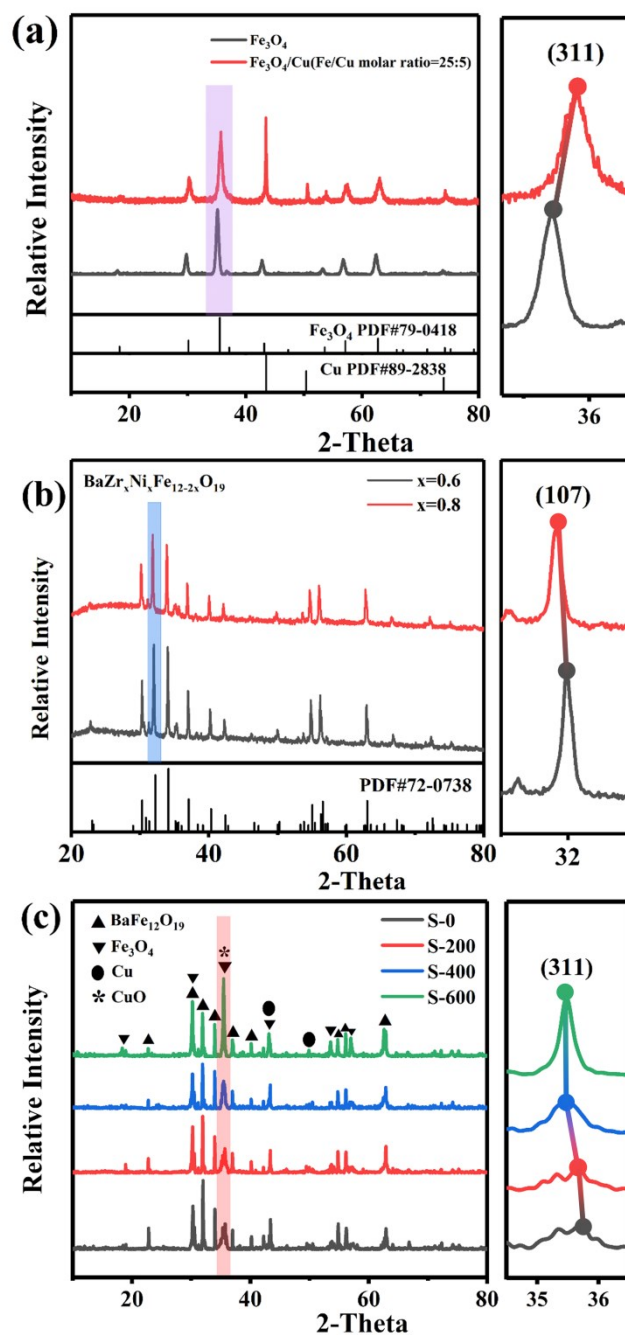


Fig. S1. XRD patterns of (a) pure Fe_3O_4 and $\text{Fe}_3\text{O}_4/\text{Cu}$ sample along with the magnified XRD patterns of (311) lattice plane; (b) $\text{BaZr}_x\text{Ni}_x\text{Fe}_{12-2x}\text{O}_{19}$ samples with $x=0.6$, and 0.8 as well as the magnified XRD patterns of (107) lattice plane; (c) S-0, S-200, S-400 and S-600 along with the magnified XRD patterns of the (311) lattice plane.

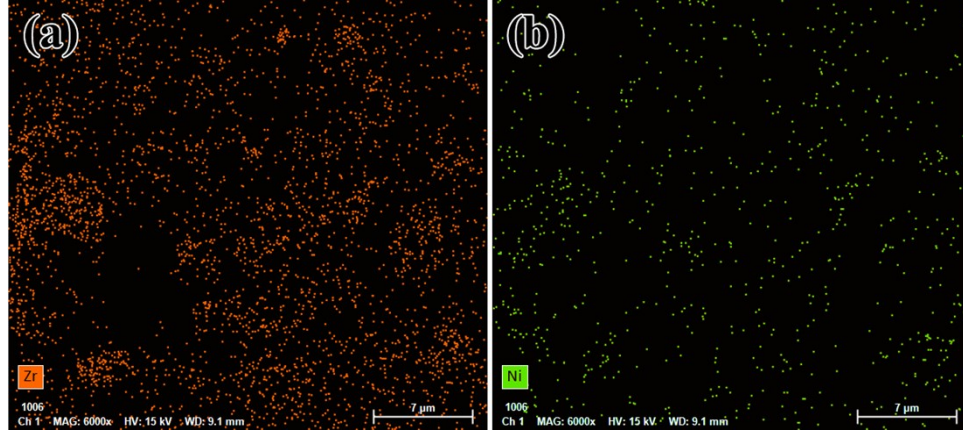


Fig. S2. The EDS element mapping of (a) Zr and (b) Ni for S-0.

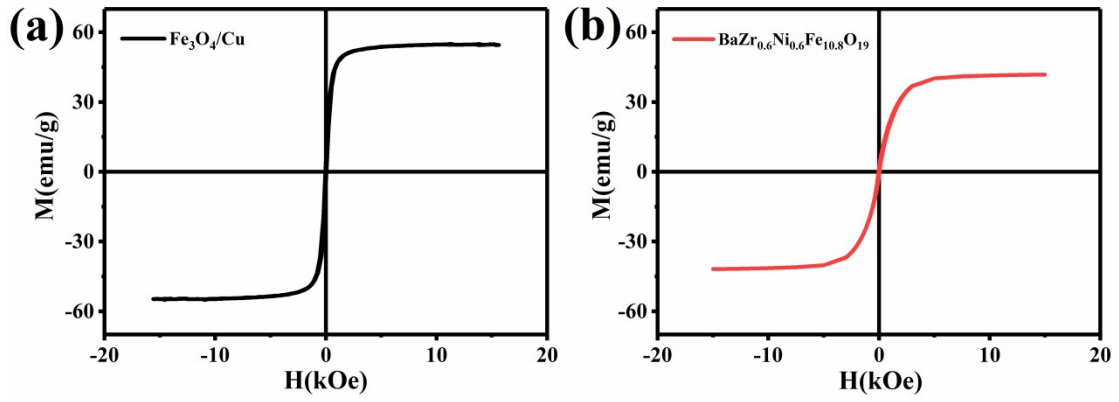


Fig. S3. Hysteresis loop of (a) $\text{Fe}_3\text{O}_4/\text{Cu}$, (b) $\text{BaZr}_{0.6}\text{Ni}_{0.6}\text{Fe}_{10.8}\text{O}_{19}$.

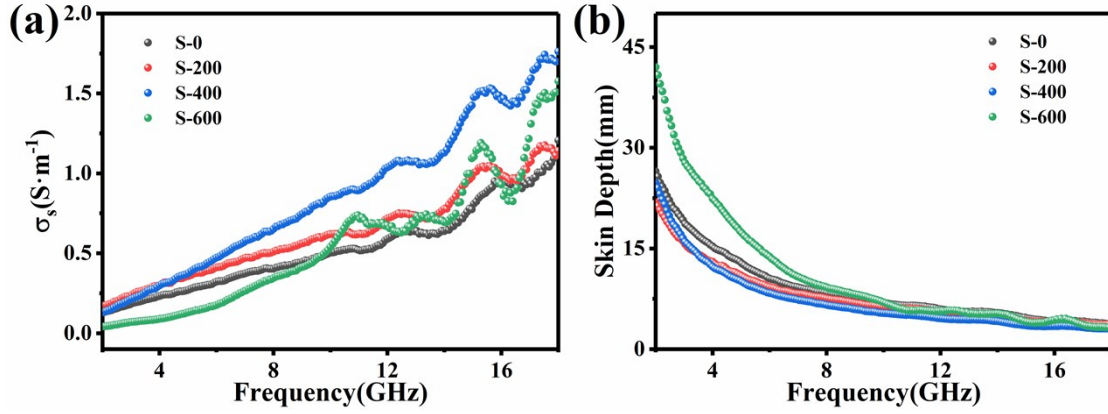


Fig. S4. (a) The AC conductivities and (b) skin depths of all samples over 2~18 GHz.